Special Issue

Atomic Layer Deposition and Atomic Layer Etching

Message from the Guest Editors

In recent years, there have been significant advances in atomic layer deposition (ALD) and atomic layer etching (ALE), which are very powerful and elegant tools in many industrial and research applications. As ALD/ALE technology matures and diversifies, it is believed to create various applications through innovation and optimization. This Special Issue of *Materials* on "Atomic Layer Deposition and Atomic Layer Etching" is intended to cover original research and critical review articles on recent advances in all aspects of ALD/ALE. Potential topics include but are not limited to the following:

- ALD applications: memory, display, energy, and emerging applications, etc.;
- ALD fundamentals: precursors and chemistry, growth, and characterization;
- Area-selective ALD and epitaxial growth of ALD;
- In situ characterization of ALD processes and materials;
- Thermal and plasma atomic layer etching (ALE).

Guest Editors

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Message from the Editor-in-Chief

Materials (ISSN 1996-1944) was launched in 2008. The journal covers twenty-five comprehensive topics: biomaterials, energy materials, advanced composites, advanced materials characterization, porous materials, manufacturing processes and systems, advanced nanomaterials and nanotechnology, smart materials, thin films and interfaces, catalytic materials, carbon materials, materials chemistry, materials physics, optics and photonics, corrosion, construction and building materials, materials simulation and design, electronic materials, advanced and functional ceramics and glasses, metals and alloys, soft matter, polymeric materials, quantum materials, mechanics of materials, green materials, general. *Materials* provides a unique opportunity to contribute high quality articles and to take advantage of its large readership.

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